

# CRASH COURSE

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10EE764

## Seventh Semester B.E. Degree Examination, May 2017 VLSI Circuits and Design

Time: 3 hrs.

Max. Marks: 100

**Note: Answer any FIVE full questions, selecting atleast TWO questions from each part.**

### PART – A

1. a. Explain the process of nMOS fabrication with neat diagrams. (10 Marks)  
 b. Discuss Moore's law with graph. (04 Marks)  
 c. Compare CMOS and Bipolar technology. (06 Marks)
  
2. a. Define  $Z_{pu}$  and  $Z_{pd}$  – show that pull-up to pull-down ratio for nMOS inverter driven through another nMOS inverter is  $Z_{pu}/Z_{pd} = 4/1$ . (10 Marks)  
 b. Explain latch-up phenomenon in p-well CMOS inverter. (06 Marks)  
 c. What is pass transistor? Give an example and write demerit of nMOS pass transistor. (04 Marks)
  
3. a. Explain Lambda based design rules for wires and minimize size transistors. (10 Marks)  
 b. Explain buried and butting contact with neat diagram. (06 Marks)  
 c. Draw the circuit and stick diagram for CMOS inverter. (04 Marks)
  
4. a. Define sheet resistance, square capacitance and delay unit. (06 Marks)  
 b. Write briefly on non-inverting type nMOS super buffer. (04 Marks)  
 c. Calculate the total area capacitance for the multilayered structure shown in Fig. Q4(c). Assume for  $5\mu\text{m}$  technology. (10 Marks)
  - i) Metal 1 to substrate :  $0.07 \times 10^{-4} \text{ pf}/\mu\text{m}^2$
  - ii) Poly silicon to substrate :  $0.1 \times 10^{-4} \text{ pf}/\mu\text{m}^2$
  - iii) Crater to channel :  $1 \times 10^{-4} \text{ pf}/\mu\text{m}^2$ .

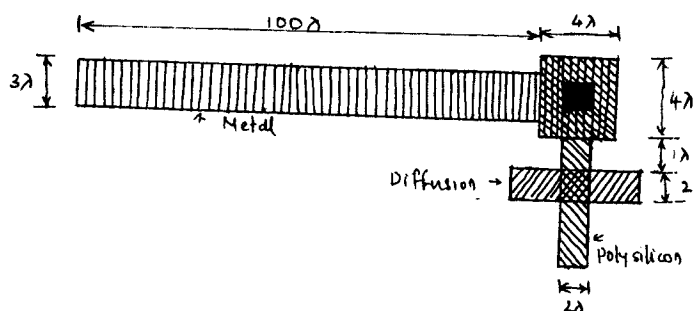


Fig. Q4(c)

### PART – B

5. a. What are different scaling models? Explain with neat diagram. (04 Marks)  
 b. Discuss limitations of scaling for interconnect and contact resistance. (06 Marks)  
 c. List any ten scaling factors for device parameters. (10 Marks)

Important Note: The candidates are advised to complete the exam paper in the first 15 minutes. Any revealing of identification, appeal to evaluator and/or equations written eg, 42+8=50, will be treated as malpractice.

- 6 a. Explain structural design approach for parity generator and draw the nMOS stick diagram of its basic cell. (10 Marks)  
b. What are the guidelines for a subsystem design process? (06 Marks)  
c. Write short note on dynamic CMOS logic. (04 Marks)
- 7 a. Explain the operation of  $4 \times 4$  barrel shifter. (10 Marks)  
b. Explain the general arrangement of 4-bit arithmetic processor. (06 Marks)  
c. List the general considerations for VLSI design. (04 Marks)
- 8 a. Show how arithmetic and logical functions are implemented using adder cell. (10 Marks)  
b. Explain some observations to design process. (06 Marks)  
c. What is regularity? Explain. (04 Marks)

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